DESCRIPTION: Model CESx128

The highly efficient Model CESx128 is the ideal for Cleaning and Etching Wafers, Photomask, and Substrates. The very reliable and cost effective system utilizes proven assortment of technologies on individual or multiple media. The CESx128 can be configured with several process dispense options from Megasonic Nozzles for DI-H₂O or Chemistries; Heaters for chemistries and DI-H₂O; Brush for Surface Agitation to Expedite Reactions, and/or DI-H₂O and much more. The Rapid and Effective Drying technique combines Variable Spin Speeds; optional Heated DI-H₂O; and Nitrogen Assist. The System is very safe, having “Rinse to pH” before access to the substrate to minimize exposure to chemistries.

FEATURES: CONTROL & SAFETY

- System Designed for Significant Control & Safety
- Up to Nine by Nine (9x9) Inch/300mm Diameter Substrate Compatibility.
- Main Spindle Assembly having DC Brushless Servo Motor for precise speed control & indexing.
- Adjustable Arm Speed and Travel Positions with Arms of Teflon Coated Stainless Steel.
- Radially Exhausted Chamber for Maximum Laminar Flow with N₂ feed at Top of the lid.
- DI-H₂O Heater for Clean & Dry Assist.
- Process containment of chemically compatible material either PVDF or optional PTFE.
- Stand-alone Polypropylene Cabinet.
- Microprocessor Control Capable of Retaining Thirty (30) Recipes having thirty (30) Steps each in Memory. Both number of Recipes & Steps are expandable upon request.
- Built in Safety Interlocks & Double Containment.
- Rinse to pH of entire process area & substrate with interlocks to prohibit access to process area & control Drain and Spindle Speed till safe.
- Push Button Lid Open/Close.
- Touch Screen Graphic User Interface (GUI) with Ease of Programming & Security Lockouts with On-Screen Error Reporting.
- Drain Diverter Valves for Chemical & House Drains
- Designed to SEMI S2/S8 Guidelines

OPTIONS: UP TO TWO OSCILLATING DISPENSE ARMS

- Various sizes & types of chucks for Wafers, Photomask, and other Substrates.
- Auto Up/Down Oscillating Adjustable Self Cleaning Brush Assembly for chemical, Surfactant, & DI-H₂O Dispenses.
- Oscillating Megasonic Nozzles & Megpies for DI-H₂O or Chemical Dispense Arm.
- Fixed or Oscillating Low Pressure Dispense with various Nozzles for DI-H₂O &/or Chemistries.
- Chemical Cabinet with weight Scale Dispense Canisters, Digital Flow Meter & Pump.
- Heater for Chemical & DI-H₂O Dispenses.
- Secondary Containment With Leak Detection
- Point of Use Mixing Systems.
- FM4910 Fire Retardant Cabinet & Process Area Materials
Model CESx128 Quad Modules with Automation